

IN THE SPECIFICATION:

Please amend the Specification as follows:

Please amend the first full paragraph on page 2 of the Specification as follows:

As a wafer storage case, for example, there has been known such construction as shown in FIGs. 9 to 11. In the figures, a wafer storage case 12 is constituted of a case body 14 housing wafers; and a lid 16 closing an upper opening section of the case body 14. There is mounted in the case body 14 a substrate-housing cassette 18 in which many wafers W are housed, as shown in FIG. 11. Note that a reference numeral 20 is a packing to be mounted along a peripheral portion of the upper opening section of the case body 14 and a reference numeral 22 is a substrate retainer mounted on the upper portion of the substrate-housing cassette 18.

Please amend the paragraph on page 18, lines 13-23 as follows:

Then, the synthetic resin surface 12a after the surfactant coating is cleaned with pure water (FIG. 3(c)). By the pure water cleaning, there are washed away particles P attached on a surface of the surfactant layer L. At this time, while the surfactant of the surfactant layer L is concurrently washed away, it is required to perform the cleaning so as to maintain a state where the surfactant layer L covers all of the synthetic resin surface 12a. If the surfactant layer L is partly lost, effective prevention of dust generation cannot be carried out as described above because a bare portion of the synthetic resin surface 12a is exposed, therefore it is necessary to perform; pure wafer water cleaning with care not to cause partial loss of the surfactant layer L.